



1763

PATENT

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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

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In re application of: Chen et al.

Attorney Docket No.:

LAM1P151/P0689

Application No.: 09/676,269

Examiner: Unassigned

Filed: September 28, 2000

Group: 1763

Title: CHAMBER CONFIGURATION FOR  
CONFINING A PLASMA#7  
4/5/02  
MW**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail to: Commissioner for Patents, Washington, DC 20231 on March 14, 2002.

Signed: \_\_\_\_\_

Agnes Spence

**RESPONSE TO RESTRICTION REQUIREMENT**Commissioner for Patents  
Washington, DC 20231

Dear Sir:

In response to the Restriction Requirement dated February 25, 2002, Applicant hereby provisionally elects, without traverse, group I, claims 1-13 to prosecute in the above-identified patent application. Although there is no traversal, Applicant respectfully requests the Examiner to reconsider the Restriction Requirement because it is the Applicant's belief that prosecuting both groups I and II would not unduly burden the Examiner. For example, group I is directed at a plasma confining assembly for minimizing unwanted plasma formations in regions outside of a process region in a process chamber and group II is directed at a plasma apparatus including a chamber and a plasma confinement assembly for preventing a plasma from forming outside of a process region.

Respectfully submitted,  
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